

References

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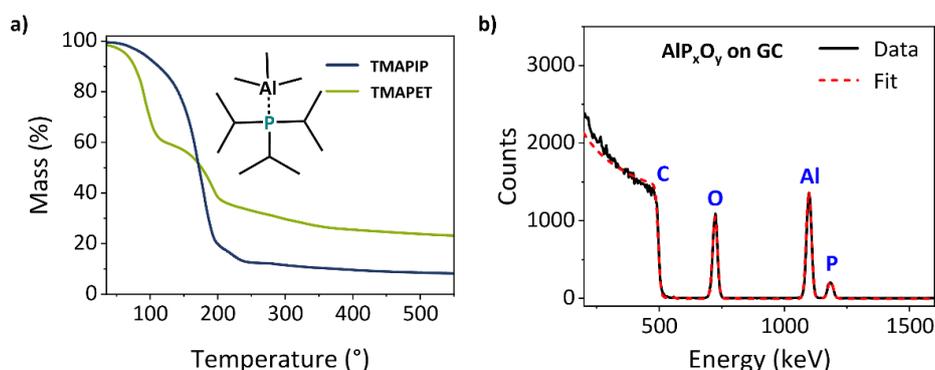


Figure 1. a) TG curves of TMAPET (green line) and TMAPIP (blue line), with the structure of TMAPIP shown as an inset. b) RBS spectrum of AlP_xO_y deposited using the dual source precursor TMAPIP on glassy carbon (GC).

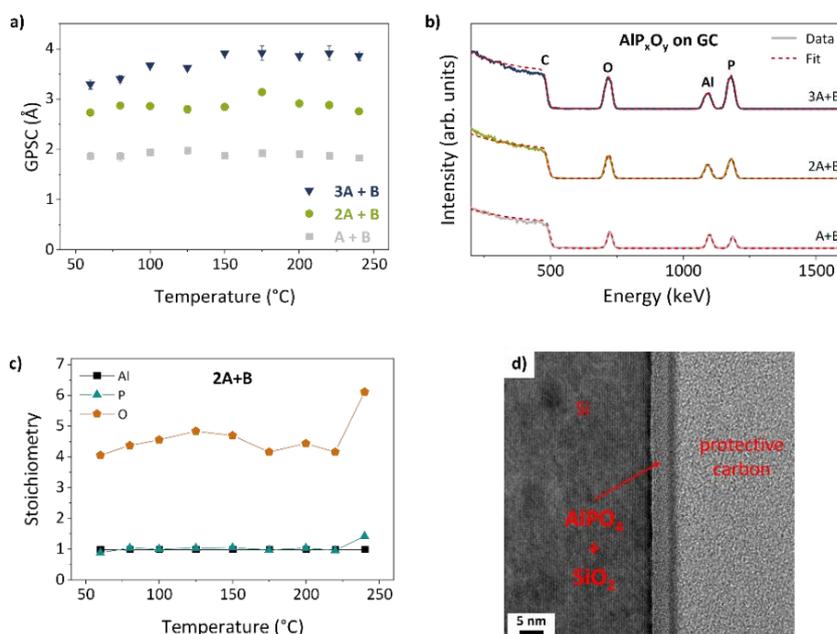


Figure 2. a) Temperature dependency of AlP_xO_y deposited on Si substrates using a PEALD supercycle of TMA and $\text{P}(\text{NMe}_2)_3$. b) RBS spectra of AlP_xO_y deposited at 150 °C using different PEALD SC sequences (bottom: A+B, middle: 2A+B, top: 3A+B) on GC. c) Stoichiometry of AlP_xO_y thin films deposited on GC using supercycle sequences consisting of two $\text{P}(\text{NMe}_2)_3$ cycles one TMA cycle, as determined by RBS. d) HRTEM image of AlPO_4 deposited on Si with 150 2A+B supercycles at 150 °C.